

Please replace the paragraph beginning at page 19, Line 17 with the following paragraph:

Any suitable algorithms may be implemented for analysis of an image. For example, an algorithm may simply compare line widths between the image and reference data. If the difference between the width of a line in the image and a width of a line in the reference image is more than a predetermined amount, a defect may be flagged by the leaf processor. The same algorithm may be used by two different leaf processors, but under varying conditions. For example, the predetermined amount may be less stringent for one leaf processor and more stringent for the other leaf processor. In sum, the algorithms used by the individual leaf processors may vary qualitatively and/or quantitatively. Several embodiments for various algorithms and inspection analysis techniques are described in U.S. patent application ~~filed on 17 December 1998~~ issued on March 4, 2003 having application patent number 6,529,621 09/213,744, entitled "Mechanisms for Making and Inspecting Reticles" by Glasser et al., which is herein incorporated by reference in its entirety.